

Impurities and Inelastic Processes in Magnetic Tunnel Junctions

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We have studied tunnel magnetoresistance (TMR) in junctions with 3d ferromagnetic electrodes. Previously we predicted that defects in the barrier would result in reduced effective polarization P of the impurity assisted current. This is confirmed experimentally in the present work: introductions of defects into the barrier drastically decreases the TMR. The degradation of magnetoresistance with bias has also been studied and shows universal features, attributed to effects of tunneling assisted by magnons and phonons, whose different role is described. Details of the bias dependence of the TMR depend on preparation procedures and well described by the model which includes assisted tunneling. Non-linear features, seen at low biases, are related to excitation of bulk modes by tunneling electrons. The analysis of factors resulting in fall-off of the TMR with bias is presented.

73.40.Gk, 73.40.Rw, 75.70.Pa, 85.70.Kh

Current through a tunnel structure with ferromagnetic electrodes is controlled by the mutual orientation of their magnetic moments. Although this concept was established in early experiments, [1–3] only recently was it demonstrated that the effect can be large at room temperatures. [4] The effect of tunnel magnetoresistance (TMR) is of fundamental interest and potentially applicable to magnetic sensors and memory devices. [3]

According to the standard picture of tunneling, the total resistance of such junctions depends exponentially on barrier parameters (thickness and barrier height). The relative *change* in resistance, however, depends only on the effective polarization of electrons in the electrodes. [1,5,6] Two pertinent problems relating to the tunnel magnetoresistance are (i) the role of defect/impurity states in the barrier and resonant tunneling via them, and (ii) the degradation of the TMR with bias.

We shall show that TMR is drastically reduced, as predicted, [6] by an introduction of impurities into the barrier. The impurities decrease polarization of tunneling electrons. Furthermore, we shall show that the degradation of TMR with increasing bias voltage is related to inelastic tunneling processes involving magnons and phonons, which play opposite roles in TMR.

Magnetoresistance (MR) is defined as the relative change in the junction conductance with respect to the change of the mutual orientation of spins from parallel (G^P) to antiparallel (G^{AP}). If the effective polarization of bulk tunneling carriers is P_{FB} , then the MR is given by Julliere's formula [1,6]

$$MR = \frac{G^P - G^{AP}}{G^{AP}} = \frac{2P_{FB}P'_{FB}}{1 - P_{FB}P'_{FB}}. \quad (1)$$

For bulk ferromagnetic electrodes, the values of polarization have been estimated from low-temperature tunneling experiments. [3] These values, as well as a straightforward calculation of the TMR due to direct tunneling between bulk ferromagnetic electrodes, [6] give a TMR of about 30%.

The formula (1) is generic and applies to physically different processes, although the corresponding effective polarizations of these processes may be very different. The presence of impurity/defect states in the barrier results in resonant tunneling of electrons. It dominates over direct tunneling when the impurity density of states exceeds approximately $10^{17} \text{cm}^{-3} \text{eV}^{-1}$. [6] The corresponding effective polarization of impurity channels is significantly lower than the bulk one, and it gives a predicted value of about 4% for TMR. [6] The much lower polarization is mainly due to mixing of the tunneling electron's wave function with that of non-polarized defect states. In the case of magnetic impurities (spin-flip centers) the TMR will be even smaller. As we report below, these predictions are in good correspondence with our observations.

We have performed a series of experiments to check the relevance of the afore-mentioned different physical mechanisms of tunneling. Junctions used were fabricated with NiFe and/or CoFe electrodes with about 2nm of plasma oxidized Al to form a barrier. The resistance change of the NiFe junctions is consistently about 30-32% with respect to the lowest resistance of the hysteresis loop (Fig. 1). Measurements of tunnel resistance as a function of external field have been performed, including the resistance change in the field as a function of bias, all at room temperature. An important result is that the value of TMR does not depend, within the accuracy of our measurements, on the thickness of the barrier, which has been varied between 2.0 to 3.3 nm of alumina. This means that the polarization of tunneling current is defined mainly by the bulk ferromagnetic electrodes and not much dependent on the thickness of the clean barrier.

To study the effect of imperfections in the barrier, the latter has been intentionally modified to incorporate defects. A uniform distribution of impurities across the barrier has been achieved by co-sputtering Au with Al instead of the usual Al only deposition described above. Two samples were prepared with 5% and 10% Au incorporated in the Al layer before plasma oxidation. This leads to a reduction of TMR down to 17% and 10%, respectively (Fig. 1). We have also prepared barriers with midlayers of NiFe and Au of thickness t . Samples with $t_{\text{midlayer}} = 0.5$ and 1 nm show zero TMR. The drastic difference between co-sputtered samples and samples with the metallic midlayer is easy to understand: only impurities very close to the center of the barrier are effective scatterers. [6] Even without spin-flip effects they suppress TMR to a small value, and the addition of spin mixing due to the exchange interaction of tunneling electrons with impurities will quickly reduce it further. Similar results for midlayers of different 3d metals have been reported. [11]

Another important issue is the behavior of TMR under bias conditions. Generally, if only direct tunneling between ferromagnetic electrodes were to take place, the TMR would smoothly degrade with bias following a parabolic law [$\text{MR}(V) \approx \text{MR}(0) - \text{const} \times V^2$]. [6] The experimentally observed degradation is considerably faster at low biases within about 0.03-0.1 V, with the conductance showing the so-called ‘zero-bias’ anomaly. [8] Our studies of TMR in a series of control junctions show that the bias dependence of normalized TMR has a rather universal behavior (Fig. 2). A plausible explanation of this behavior is inelastic tunneling assisted by emission of bosons (phonons and magnons). [8] Whereas the role of magnons obviously includes spin mixing that reduces TMR, there might be a misconception that phonons are not coupled to spin and, therefore, play no role in TMR. This is not the case, as the probability of any tunneling event is proportional to initial and final densities of states (DOS). Since the DOSs are different for majority and minority carriers, *any* boson-assisted event would change TMR. But since phonons do not induce spin mixing, they *increase* the TMR, as opposed to magnons that always tend to decrease the TMR. In addition, we note that Kondo-like scattering on magnetic impurities [9] (formally third order in exchange constant) operates at very low biases, if at all, and usually does not fit experimental $I - V$ curves. [10]

Magnon-assisted current in, for example, parallel configuration at bias V and temperature T is given by the following expression [13]:

$$I_{\text{P}}^x(V, T) = \frac{2\pi e}{\hbar} \sum_{\mathbf{q}\alpha} X^\alpha \left(g_{\uparrow}^L g_{\downarrow}^R \times (eV + \omega) \left[\frac{N_\omega}{1 - \exp(-\beta(eV + \omega))} + \frac{N_\omega + 1}{1 - \exp(\beta(eV + \omega))} \right] \right. \\ \left. + g_{\downarrow}^L g_{\uparrow}^R \times (eV - \omega) \left[\frac{N_\omega + 1}{1 - \exp(-\beta(eV - \omega))} + \frac{N_\omega}{1 - \exp(\beta(eV - \omega))} \right] \right), \quad (2)$$

where $N_\omega = [\exp(\beta\omega) - 1]^{-1}$, $\beta = 1/T$, $\omega = \omega_{\mathbf{q}}^\alpha$ and X^α is the incoherent tunnel exchange (electron-magnon) vertex with all momenta parallel to the barrier integrated out, $g^{L(R)}$ marks the corresponding electron density of states on the left (right) electrode, and $\alpha = L, R$. Analogous expression can be easily obtained for the AP configuration. As follows from Eq. (2), the magnon-assisted inelastic tunneling current at $T = 0$ is

$$I_{\text{P}}^x = \frac{2\pi e}{\hbar} \sum_{\alpha} X^\alpha g_{\downarrow}^L g_{\uparrow}^R \int d\omega \rho_{\alpha}^{\text{mag}}(\omega) (eV - \omega) \theta(eV - \omega), \\ I_{\text{AP}}^x = \frac{2\pi e}{\hbar} \left[X^R g_{\uparrow}^L g_{\uparrow}^R \int d\omega \rho_R^{\text{mag}}(\omega) (eV - \omega) \theta(eV - \omega) \right. \\ \left. + X^L g_{\downarrow}^L g_{\downarrow}^R \int d\omega \rho_L^{\text{mag}}(\omega) (eV - \omega) \theta(eV - \omega) \right], \quad (3)$$

where $\rho_{\alpha}^{\text{mag}}(\omega)$ is the magnon density of states that has the general form $\rho_{\alpha}^{\text{mag}}(\omega) = (\nu + 1)\omega^\nu / \omega_0^{\nu+1}$, where the exponent ν depends on the type of spectrum and may be determined from a fit to experimental data, ω_0 is the maximum magnon frequency, and $\theta(x)$ is the step function.

For phonon-assisted current at $T = 0$ we obtain

$$I_{\text{P}}^{\text{ph}} = \frac{2\pi e}{\hbar} \sum_{a\alpha} g_a^L g_a^R \int d\omega \rho_{\alpha}^{\text{ph}}(\omega) \\ \times P^{\alpha}(\omega) (eV - \omega) \theta(eV - \omega), \quad (4)$$

$$I_{\text{AP}}^{\text{ph}} = \frac{2\pi e}{\hbar} \sum_{a\alpha} g_a^L g_{-a}^R \int d\omega \rho_{\alpha}^{\text{ph}}(\omega) \\ \times P^{\alpha}(\omega) (eV - \omega) \theta(eV - \omega), \quad (5)$$

where $P(\omega)$ is the phonon vertex proportional to a deformation potential, $P(\omega)/X = \gamma\omega/\omega_D$, γ is a constant, ω_D is the Debye frequency, a is the spin index, ρ_α^{ph} is the phonon DOS, α here marks electrodes and the barrier.

The elastic and inelastic contributions together will define the total junction conductance $G = G(V, T)$ as a function of the bias V and temperature T . We find that the inelastic contributions from magnons and phonons (3)-(5), respectively, grow as $G^x(V, 0) \propto (|eV|/\omega_0)^{\nu+1}$ and $G^{ph}(V, 0) \propto (eV/\omega_D)^4$ at low biases. These contributions saturate at higher biases: $G^x(V, 0) \propto 1 - \frac{\nu+1}{\nu+2} \frac{\omega_0}{|eV|}$ at $|eV| > \omega_0$; $G^{ph}(V, 0) \propto 1 - \frac{4}{5} \frac{\omega_D}{|eV|}$ at $|eV| > \omega_D$. This behavior would lead to sharp features in the $I - V$ curves on a scale of 30-100 mV (Fig. 2).

To highlight the opposite effects of phonons and magnons on the TMR, let us consider the case of the same electrode materials and denote $D = g_\uparrow$ and $d = g_\downarrow$. We see that $G_P^x(V, 0) - G_{AP}^x(V, 0) \propto -(D - d)^2(|eV|/\omega_0)^{\nu+1} < 0$, whereas $G_P^{ph}(V, 0) - G_{AP}^{ph}(V, 0) \propto +(D - d)^2(eV/\omega_D)^4 > 0$, i.e. spin-mixing due to magnons *decreases* the TMR, whereas phonons tend to reduce the negative effect of magnon emission on the magnetoresistance.

Finite temperature gives contributions of the same respective sign as written above. For magnons: $G_P^x(0, T) - G_{AP}^x(0, T) \propto -(D - d)^2(-TdM/dT) < 0$, where $M = M(T)$ is the magnetic moment of the electrode at a given temperature T . The phonon contribution is given by a standard Debye integral with the following results: $G_P^{ph}(0, T) - G_{AP}^{ph}(0, T) \propto +(D - d)^2(T/\omega_D)^4 > 0$ at $T \ll \omega_D$, and $G_P^{ph}(0, T) - G_{AP}^{ph}(0, T) \propto +(D - d)^2(T/\omega_D)$ at $T \gtrsim \omega_D$. It is worth mentioning that the magnon excitations are usually cut off by, for instance, the anisotropy energy K_{an} at some ω_c . Therefore, at low temperatures the conductance at small biases will be almost constant.

The experimental data in Fig. 2(a) has been fitted by expressions (3)-(5) with the inclusion of the bias dependence of direct tunneling current. The figure shows the bias dependence of the direct tunnel current (broken line) is almost parabolic and does not replicate the data. The inclusion of inelastic events, however, produces a very good fit to the experimental data. Moreover, we extract an exponent for the magnon DOS which happens to be close to $\nu \approx \frac{1}{2}$. This square-root law is characteristic of usual bulk magnons which, therefore, are of major importance in the ‘zero bias’ anomaly of the TMR. Two-dimensional magnons, if they were important, would result in a linear cusp at zero bias ($\nu = 0$), which has not generally been observed. [14] The present fit shows that the bulk, rather than surface magnons, are responsible for the shape of the $I - V$ curves at low biases (Fig. 2).

The effect of preparation scheme and impurities is further illustrated by Fig. 2(b). There we compare the data for plasma oxidized, radio frequency (rf) sputtered Co/AIO_x/NiFe samples, together with NiFe/AIO_x/NiFe with 5% and 10% of co-sputtered Au in the barrier. In order to understand this data for the bias dependence of TMR, it is helpful to cast (3)-(5) in the form $MR(V) = [MR_0(V) - p_x B_1(V)]/[1 + p_x B_2(V)]$, where $MR_0(V)$ is the tunnel magnetoresistance due to direct tunneling, B_1 and B_2 are smooth positive functions of the voltage bias, and $p_x \propto X/G_{AP}^0$ is the parameter inversely proportional to an elastic conductance for the antiparallel configuration. Consequently, the parameter p_x is larger for more resistive junctions. Our rf sputtered junction were five times more resistive than the plasma oxidized ones, resulting in a steeper decrease of their TMR with bias [Fig. 2(b)]. We find that in all cases the data is clearly non-linear at low biases, supporting our conclusion about the dominating role of the *bulk* magnon excitations in the voltage dependence of the tunnel magnetoresistance (Fig. 2).

The present results demonstrate over 30% completely stable resistance change in magnetic tunnel junctions at room temperature. Presence of impurities, defect states in the barrier, significantly reduces the magnetoresistance. We expect that any inhomogeneity in the barrier would lead to similar results. The rf sputtered junctions are likely to have a larger density of defect states in the barrier, and, consequently, smaller tunnel magnetoresistance as compared to plasma oxidized junctions. It is demonstrated, that the inelastic processes are responsible for the unusual shape of the $I - V$ curves at low biases, and their temperature behavior, which is also affected by impurity-assisted tunneling. The fall-off of tunnel magnetoresistance is faster in more resistive rf sputtered junctions. Trends and details of the bias dependence of the TMR are well described by the present theoretical model. Analysis of the data suggests that the anomalies are due to emission of bulk magnons and phonons. Further study is required to demonstrate to what extent these characteristics can be controlled to improve performance of the junctions.

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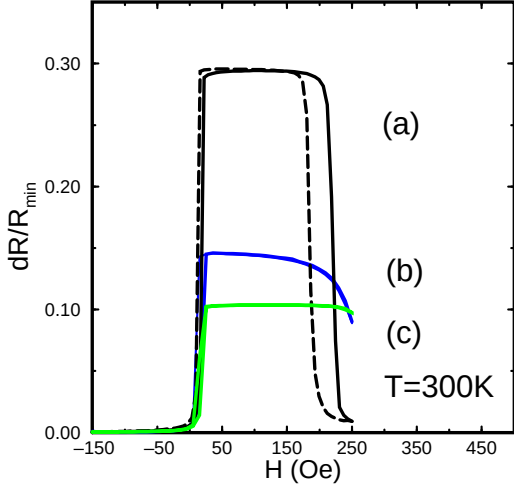


FIG. 1. Room temperature magnetoresistance (dR/R_{min}) curves for tunnel junctions prepared as described in text (thicknesses in nm): (a) junction NiFe/2AlO_x/NiFe, area 1800 μm^2 , $R_{min} = 10 \text{ k}\Omega$; (b) junction with co-sputtered Au in a barrier NiFe/1.9AlO_x0.1Au/NiFe, area 1800 μm^2 , $R_{min} = 33.5 \text{ k}\Omega$. (c) junction with co-sputtered Au in a barrier NiFe/1.8AlO_x0.2Au/NiFe, area 1800 μm^2 , $R_{min} = 17 \text{ k}\Omega$. Solid curves: forward sweep in field, broken curve: backward sweep. Switching field $H_{sw} = 250 \text{ Oe}$ is due to exchange biasing by MnFe. Samples with NiFe midlayer (not shown) demonstrate zero magnetoresistance.

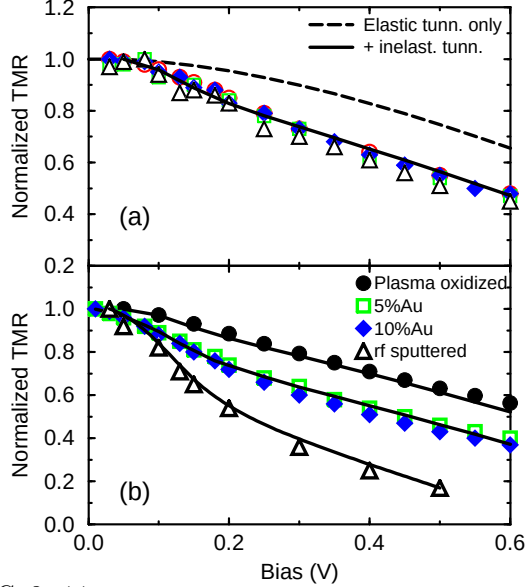


FIG. 2. (a) Experimental data for the magnetoresistance of CoFe/Al₂O₃/NiFe tunnel junctions. The junctions were prepared similar to those described in text, with the bottom electrode containing only Co or CoFe, with $dR/R_{min}=0.10$. The fit includes elastic and inelastic (assisted by magnons and phonons) tunneling. The fit gives a magnon DOS very close to $\propto \omega^{0.5}$, which is characteristic of the bulk spectrum. (b) Experimental data for the magnetoresistance of plasma oxidized and rf sputtered CoFe/Al₂O₃/NiFe tunnel junctions, and NiFe/Al₂O₃/NiFe junctions with 5% and 10% of co-sputtered Au. In all cases the bias dependence at low voltages is non-linear, indicating the emission of the bulk magnons. Exponent in magnon spectrum was again close to the bulk one $\omega^{0.5}$, parameter p_x varied following changes in junction conductance (see text).